EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L12	9	silicid$5 near3 gate adj electrode and polysilicon adj (material film layer) and alloy and first adj metal and second adj metal and anneal$3 and pattern$3.clm.	US-PGPUB	OR	ON	2007/03/28 20:14

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S142	130	438/581.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 01:42
S143	107	S142 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S144	99	S143 and (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 17:10
S145	291	438/647.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S146	2048	438/647,655.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S147	1950	S146 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S148	313	438/657.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S149	1806	438/655.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:20
S150	1720	S149 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 09:30

S15 1	1475	S150 and (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 02:21
S15 2	2048	438/647,655.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 09:55
S15 3	1950	S152 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 09:55
S15 4	0	257/e21.438,e21.439	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:24
S15 5	1994	257/e21.438,e21.439.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:24
S15 6	1673	S155 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:24
S15 7	6880	gate near2 (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 17:10
S15 8	8637	polysilicon near2 (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 17:11
S15 9	758	S157 with S158	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 17:11
S16 0	14	S159 same first adj metal and second adj metal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 17:25

S16 1	9	S159 same (first adj metal and second adj metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:36
S16 2	544	438/664.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 10:07
S16 3	544	438/664.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 09:30
S16 4	481	S163 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 10:07
S16 5	0	("2002/0072232").URPN.	USPAT	OR	OFF	2007/03/28 09:43
S16 6	18	("4337476" | "4378628" | "4568565" | "4897368" | "4971655" | "5240739" | "5376405" | "5470794" | "5593924" | "5608266" | "5665646" | "5739573" | "5828131" | "5874351" | "5997634" | "6054387" | "6090708" | "6376372"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 09:47
S16 7	4	("4568565" | "4971655" | "5240739" | "5376405").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 09:49
S16 8	0	("6841474").URPN.	USPAT	OR	OFF	2007/03/28 09:51
S16 9	5	("20030139061" | "5135608" | "6191463" | "6417104" | "6537910"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 09:55
S17 0	753	438/682.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 10:26
S17 1	597	S170 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:38

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S17 2	224	438/721,755.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 10:26
S17 3	216	S172 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 10:26
S17 4	17	("4704783" | "5103272" | "5183782" | "5268330" | "5320975" | "5322806" | "5428244" | "5438006" | "5472896" | "5492597" | "5512502" | "5518942" | "5518958" | "5656546" | "5665646" | "5728625" | "6137130").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 13:12
S17 5	0	("6613673").URPN.	USPAT	OR	OFF	2007/03/28 13:20
S17 6	1402	silicid$3 near3 gate adj electrode	USPAT	OR	OFF	2007/03/28 13:20
S17 7	30413	polysilicon adj (material layer film)	USPAT	OR	OFF	2007/03/28 13:21
S17 8	32200	gate adj oxide	USPAT	OR	OFF	2007/03/28 13:21
S17 9	507	alloy near5 (first adj metal and second adj metal)	USPAT	OR	OFF	2007/03/28 13:22
S18 0	1	S176 and S177 and S178 and S179	USPAT	OR	OFF	2007/03/28 13:23
S18 1	5	S177 and S178 and S179	USPAT	OR	OFF	2007/03/28 13:28
S18 2	548	S177 and S178 and metal near5 alloy	USPAT	OR	OFF	2007/03/28 13:28
S18 3	548	S177 and S178 and (metal near5 alloy)	USPAT	OR	OFF	2007/03/28 13:52
S18 4	38	S177 and S178 same (metal near5 alloy)	USPAT	OR	OFF	2007/03/28 13:37
S18 5	6880	gate near2 (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:50
S18 6	8637	polysilicon near2 (silicide salicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:36

S18 7	175	S185 and S186 and (first adj metal and second adj metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:36
S18 8	23	S187 and (metal near5 alloy)	USPAT	OR	OFF	2007/03/28 13:37
S18 9	22	S188 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:57
S19 0	5	("5723893" | "6147388" | "6180501" | "6277719" | "6465312").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 13:49
S19 1	8205	S177 same S178	US-PGPUB; USPAT; USOCR	OR	OFF	2007/03/28 13:49
S19 2	1815	S191 same (silicid$6 salicid$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:51
S19 3	84464	(silicid$6 salicid$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:51
S19 4	72958	(metal near5 alloy)	USPAT	OR	OFF	2007/03/28 13:52
S19 5	0	S177 with S178 with S193 with S194	USPAT	OR	OFF	2007/03/28 13:53
S19 6	1179	S177 with 17same (S193 with S194)	USPAT	OR	OFF	2007/03/28 13:53
S19 7	1	S177 with S178 same (S193 with S194)	USPAT	OR	OFF	2007/03/28 13:54
S19 8	7	S177 same S178 same (S193 with S194)	USPAT	OR	OFF	2007/03/28 13:55
S19 9	9	S177 same S178 same (S193 same S194)	USPAT	OR	OFF	2007/03/28 13:56
S20 0	2	S199 not S198	USPAT	OR	OFF	2007/03/28 13:55
S20 1	95	S177 same S178 and (S193 same S194)	USPAT	OR	OFF	2007/03/28 13:57
S20 2	95	S201 and S177	USPAT	OR	OFF	2007/03/28 13:56

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S20 3	86	S202 not S199	USPAT	OR	OFF	2007/03/28 13:57
S20 4	84	S203 and @ad<"20040301"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 14:22
S20 5	0	silicid$5 and gate adj electroce and polysilicon adj (material film layer) and alloy and first adj metal and second adj metal and anneal$3 and pattern$3.clm.	US-PGPUB	OR	ON	2007/03/28 14:25